Abstract of the Disclosure

Provided is a method of treating a surface of a substrate used in a biochemical reaction system, the method including forming a polymer film on the surface by vapor deposition of a compound of formula (1) below and a compound of formula (2) below:

$$(RO)_3 - Si - (CH_2)_{p_1} - X$$
 ...(1)

$$(RO)_3 - Si - (CH_2)_{n2} - (CF_2)_m - X$$
 ...(2)

10

5

wherein R is one of a methyl group and an ethyl group, X is one of a methyl group and a trifluoromethyl group, n1 is an integer from 1 to 3, n2 is an integer from 1 to 10, and m is an integer from 1 to 10.